

# PATENT ABSTRACTS OF JAPAN

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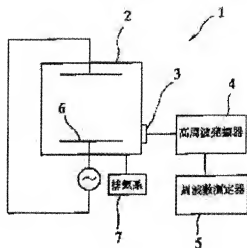
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## (54) DRY ETCHING APPARATUS

### (57)Abstract:

**PROBLEM TO BE SOLVED:** To exactly determine cleaning-start time and cleaning-end time.

**SOLUTION:** An etching apparatus 1 has a sensor in an etching processing chamber 2. Cleaning-start time is determined based on the volume of deposition of reaction product deposited on the sensor while a plurality of substrates are etched by using this dry etching apparatus 1. The change of the volume of deposition of the reaction product is measured while the etching apparatus 1 is subjected to plasma cleaning, and cleaning-end time is determined based on a point where the change of the volume of deposition has become small.



## LEGAL STATUS

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